

Title (en)

SYSTEM AND METHOD TO CORRECT FOR DISTORTION CAUSED BY BULK HEATING IN A SUBSTRATE

Title (de)

SYSTEM UND VERFAHREN ZUR KORREKTUR VON DURCH VOLUMENEUFHEIZUNG IN EINEM SUBSTRAT VERURSACHTEN VERZERRUNGEN

Title (fr)

SYSTEME ET PROCEDE DE CORRECTION DE LA DISTORSION PROVOQUEE PAR UN CHAUFFAGE DE MASSE DANS UN SUBSTRAT

Publication

**EP 1095393 A2 20010502 (EN)**

Application

**EP 00923351 A 20000412**

Priority

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Abstract (en)

[origin: WO0062324A2] An electron beam writing system includes an electron beam patterning machine operable to emit an electron beam to form a pattern on a substrate. A computer control system, coupled to the electron beam patterning machine, has a plurality of pre-computed distortion maps. Each distortion map describes expected distortions of the substrate caused by bulk heating resulting from exposure to the electron beam. The computer control system controls the electron beam patterning machine using the distortion maps in order to adjust for the expected distortions.

IPC 1-7

**H01J 37/317**

IPC 8 full level

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